

## Бடா SロபГсе

Our smallest ion beam source, the 6 cm RF can provide all the benefits of radio frequency ion source technology in a smaller, more compact, and less expensive form. With a maximum beam current of 200 mA at 1500 V , the 6 cm source is ideal for research and smaller production systems.

This source also finds a home in etch and ion beam figuring (IBF) systems with its highly divergent or highly convergent grid options. The body of this source is not water-cooled, thus requiring only two feedthroughs - RF power and DC Bias/Gas. Designed around the flexibility of internal mounting, the 6 cm source is also capable of being mounted directly to a flange for process flexibility. As with all RF sources, the 6 cm source can be run with both inert and reactive gases, making the 6 cm ideal for any ion beam process.


## INTERNRL MOUNT-

Using an Internal Mount configuration places the ion source loosely inside the vacuum chamber, allowing angular (pointing) adjustment to suit process needs. The maximum distance from the RF vacuum feedthrough for this configuration is 18 -inches. This option allows some freedom of location of the ion source and the ability to use multiple smaller feedthroughs instead of one large feedthrough. The standard flanges for this configuration are two 2.75 inch Conflat. Other flange combinations are available. The RF Matching Network mounts directly to the RF feedthrough.

